

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
5 January 2006 (05.01.2006)

PCT

(10) International Publication Number
WO 2006/001516 A1

- (51) International Patent Classification⁷: G03F 7/039, B41J 2/16
- (21) International Application Number: PCT/JP2005/012161
- (22) International Filing Date: 24 June 2005 (24.06.2005)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data: 2004-190479 28 June 2004 (28.06.2004) JP
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- (81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.
- (84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

— with international search report

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

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(54) Title: PHOTSENSITIVE RESIN COMPOSITION, METHOD OF FORMING LEVEL DIFFERENCE PATTERN USING THE PHOTSENSITIVE RESIN COMPOSITION, AND METHOD OF PRODUCING INK JET HEAD

(57) Abstract: To provide a positive type photosensitive resin composition, containing at least an acrylic resin having a carboxylic anhydride structure in a molecule, and a compound that generates an acid when irradiated with light.

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